

REMARKS

Claims 1-15 and 21-23 are pending in the present Application. Claims 1, 6 and 7 have been amended, Claims 24-32 have been added, leaving Claims 1-15 and 21-32 for consideration upon entry of the present Amendment.

Support for the amendment to Claims 1, 6 and 7 can at least be found in the specification at page 16, lines 1-8.

Support for new Claims 24-26 can at least be found in the claims as originally filed and in Figs. 3B-3E and the corresponding description in the specification.

Support for new Claims 27-32 can at least be found in Figs. 2 and 3B-3E and the corresponding description in the specification.

No new matter has been introduced by these amendments. Reconsideration and allowance of the claims are respectfully requested in view of the above amendments and the following remarks.

Claim Rejections Under 35 U.S.C. § 103(a)

Claims 1-6, 21 and 22 stand rejected under 35 U.S.C. § 103(a), as allegedly being unpatentable over Applicant's admitted prior art Figures 1A-1B and corresponding discussion in the specification in view of Fukuda (U.S. Patent No. 5,880,035).

Claims 7-15 and 23 stand rejected under 35 U.S.C. § 103(a), as allegedly being unpatentable over Applicant's admitted prior art Figures 1A-1B and corresponding discussion in the specification in view of Fukuda (U.S. Patent No. 5,880,035) and further in view of Paranjpe et al. (U.S. Patent No. 5,580,385).

These rejections are moot in light of Applicant's claim amendments.

Nevertheless, Applicant respectfully requests that the Examiner consider the following remarks.

In Applicant's presently claimed invention, a first etching process is applied using a fluorine-based gas with respect to a first one of the substrates to be processed and a second etching process is applied using a mixture gas of chlorine and oxygen in the same chamber. Because the first and second etching processes are applied in the same chamber, when the first etching process is applied to the second one of the substrates, the etching product created in

the previous second etching process for the first substrate can be automatically cleaned.

None of the above-cited references, either alone or in combination, teach or suggest types of etching processes and automatically cleaning of the product created in the previous etching process in the subsequent etching process. In particular, while Fukuda teaches a plurality of etching steps with differing conditions, Fukuda fails to teach or suggest whether or not these steps are applied in the same chamber. In addition, an embodiment of Fukuda clearly discloses that the first etching step and the second etching step are applied in different etching chambers.

AAPA and Paranjpe fail to teach or suggest application of a plurality of etching processes to one layer.

For at least these reasons, even if combined, the combined references would at least fail to teach or suggest forming of a gate electrode by a first and second etching process in the same chamber. Since the combined references fail to teach or suggest at least one claimed element, Claims 1-15 and 21-23 are non-obvious and are therefore allowable.

New Claims

None of the above cited references, either alone or in combination, teach or suggest the structure described in new independent Claims 24-26. More particularly, they do not teach or suggest that the ashing of the mask is lower and an anisotropic etching process is applied to the gate electrode layer in the first etching process and the ashing of the mask is higher and an isotropic etching process is applied in the second etching process.

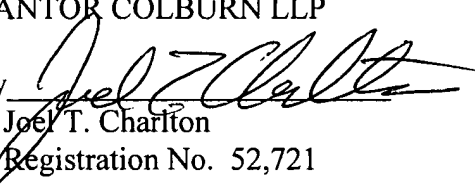
In view of the foregoing, it is respectfully submitted that the instant application is in condition for allowance. Accordingly, it is requested that this application be allowed and a Notice of Allowance issued. If the Examiner believes that a telephone conference with Applicant's attorneys would be advantageous to the disposition of this case, the Examiner is cordially requested to telephone the undersigned.

If there are any additional charges with respect to this Amendment or otherwise, please charge them to Deposit Account No. 06-1130.

Respectfully submitted,

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By


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